

What Is Claimed Is:

1. A method of fabricating a liquid crystal display device having first and second substrates, the method comprising the steps of:

forming a gate line on the first substrate;

sequentially forming a first insulating layer, an amorphous silicon layer, and a metal layer on the first substrate;

patterning the metal layer to form a data line;

forming a second insulating layer on the data line;

patterning the second insulating layer and the amorphous silicon layer to form a passivation layer and an active layer, respectively;

forming a pixel electrode at a pixel region defined by the gate and data lines;

assembling the first substrate and the second substrate having a black matrix thereon, wherein the black matrix vertically overlaps at least one boundary line defined by different exposures during step-and-repeat exposure processes; and

forming a liquid crystal layer between the first and second substrates.

2. The method of claim 1, wherein the boundary line is disposed over the gate line and the data line.

3. A method of fabricating a liquid crystal display device having first and second substrates, comprising:

forming a gate line on the first substrate;

forming a gate insulating layer on the first substrate including the gate line;

forming an amorphous silicon layer on the gate insulating layer;

forming a data line on the amorphous silicon layer;

forming an insulating layer on the amorphous silicon layer including the data line;

forming a photoresist layer having first, second, and third portions on the insulating layer, wherein the first portion has a thickness greater than the second portion, and the third portion exposes a portion of the insulating layer;

selectively removing the insulating layer and the amorphous layer to form a passivation layer on the data line and an active layer below the data line;

forming a pixel electrode on the gate insulating

layer;

forming a black matrix over the second substrate; and  
assembling the first and second substrates to  
substantially overlap at least one boundary line and the  
black matrix in a vertical direction, wherein the boundary  
lines is defined during step-and-repeat exposures at  
different times.

4. The method of claim 3, wherein the pixel  
electrode has a stitch line therein.

5. The method of claim 3, wherein the gate  
insulating layer has a stitch line therein.

6. The method of claim 3, wherein the exposed  
portion of the insulating layer vertically overlaps the  
gate line.

7. A liquid crystal display device comprising:

first and second substrates facing into each other;

a gate line on the first substrate;

a gate insulating layer on the first substrate

including the gate line;

**THE**

- a first insulating layer on the gate line;
- a silicon layer on the first insulating layer;
- a data line on the silicon layer, the data line crossing the gate line;

a pixel electrode at a pixel region defined by the gate and data lines;

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$\frac{1}{\sqrt{2}} \begin{pmatrix} 1 & i \\ 0 & 1 \end{pmatrix}$

[illegible]